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What is claimed is:

- 1. An apparatus for removing impurities from effluent waste gas streams, comprising:
 - (a) a treatment chamber having an inlet for introducing the effluent waste gas streams and an outlet;
 - (b) a spraying device for spraying liquid disposed in said treatment chamber to form a plurality of liquid films, each of which are formed vertically and spaced from each other; and
 - (c) a blower for sucking the waste gas stream upwardly through the plurality of spaced liquid films in which a portion of the impurities in the waste gas streams is mixed with the liquid to form a liquid mixture and simultaneously the waste gas stream is humidified, wherein the liquid mixture flows downward and the humidified waste gas is sucked out from the outlet of said treatment chamber.
- 2. The apparatus as claimed in claim 1, further comprising a tank disposed under said treatment chamber for receiving the liquid mixture.
- 3. The apparatus as claimed in claim 1, wherein said spraying device includes a pipe disposed in the center of said treatment chamber having a nozzle from which the liquid is sprayed out, and a plate member disposed on the opposite side of said nozzle in a manner that the sprayed-out liquid impinges on said plate member to form, the liquid film.

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- The apparatus as claimed in claim 3, further comprising a device for controlling the level of the liquid mixture, the flow rate of the effluent waste gas streams passing through said treatment chamber, and the flow rate of the liquid coming out from nozzles of said spraying means.
- 4. An apparatus for removing impurities from effluent waste gas streams, comprising:
 - (a) a treatment chamber having an inlet for introducing the effluent waste gas streams and an outlet;
 - (b) a spraying device for spraying liquid disposed in said treatment chamber to form a plurality of liquid films, each of which are formed vertically and spaced from each other;
 - (c) a blower for sucking the waste gas stream upwardly through the plurality of spaced liquid films in which a portion of the impurities in the waste gas streams is mixed with the liquid to form a liquid mixture and simultaneously the waste gas stream is humidified, wherein the liquid mixture flows downward and the humidified waste gas is sucked out from the outlet of said treatment chamber; and
 - (d) a dehumidifying device for dehumidifying the humidified waste gas streams sucked from the outlet, disposed above said treatment chamber.
 - 5. The apparatus as claimed in claim 5, wherein said dehumidifying device comprises a chamber having a plurality of perforated buffer plates disposed along the longitudinal axis thereof, each of which is disposed therein and spaced apart; and a plurality of filtering

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- 6 members disposed along the longitudinal axis thereof,
 7 each of which is disposed therein and spaced apart.
- in claim 6, wherein claimed said 6. The apparatus as 1 is of filtering disposed downstream the members 2 perforated buffer plates. 3
- 7. The apparatus as claimed in claim 5, further comprising a tank disposed under said treatment chamber for receiving the liquid mixture.
 - 8. The apparatus as claimed in claim 5, wherein said spraying device includes a pipe disposed in the center of said treatment chamber having a nozzle from which the liquid is sprayed out, and a plate member disposed on the opposite side of said nozzle in a manner that the sprayed-out liquid impinges on said plate member to form the liquid film.
 - 9. The apparatus as claimed in claim 5, further comprising a device for controlling the level of the liquid mixture, the flow rate of the effluent waste gas streams passing through said treatment chamber, and the flow rate of the liquid coming out from nozzles of said spraying means.
- 1 10. The apparatus as claimed in claim 5, wherein said liquid is water.
- 1 11. The device as claimed in claim 5, wherein the waste gas streams are from semiconductor etch and deposition processes.